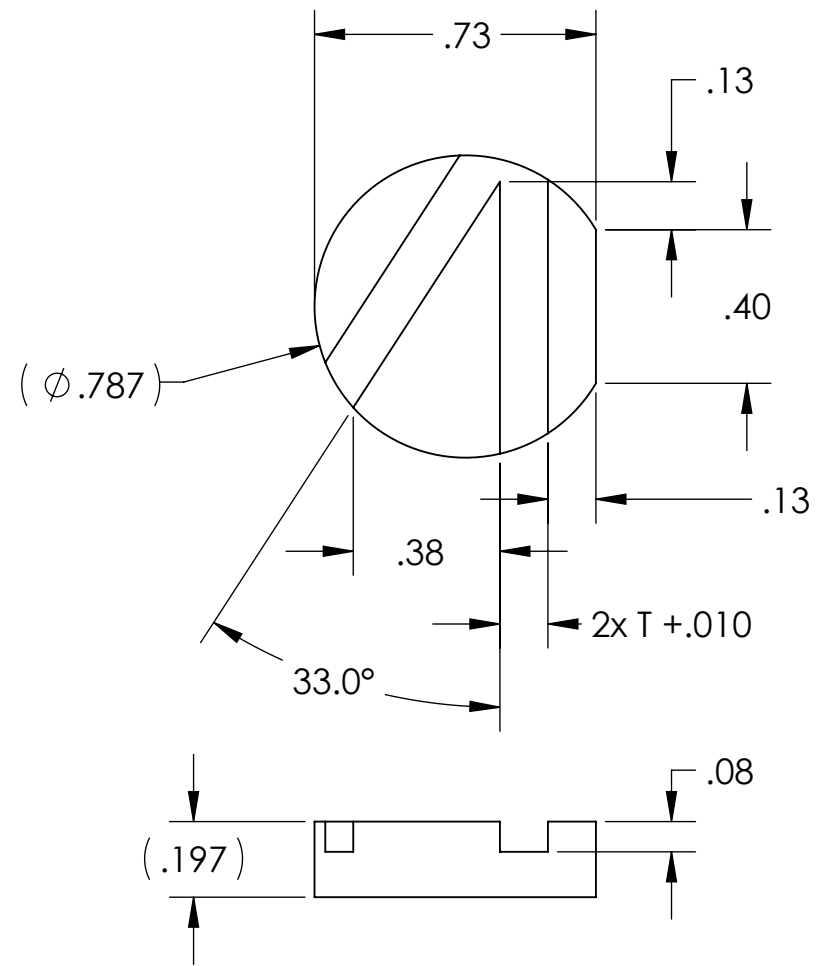


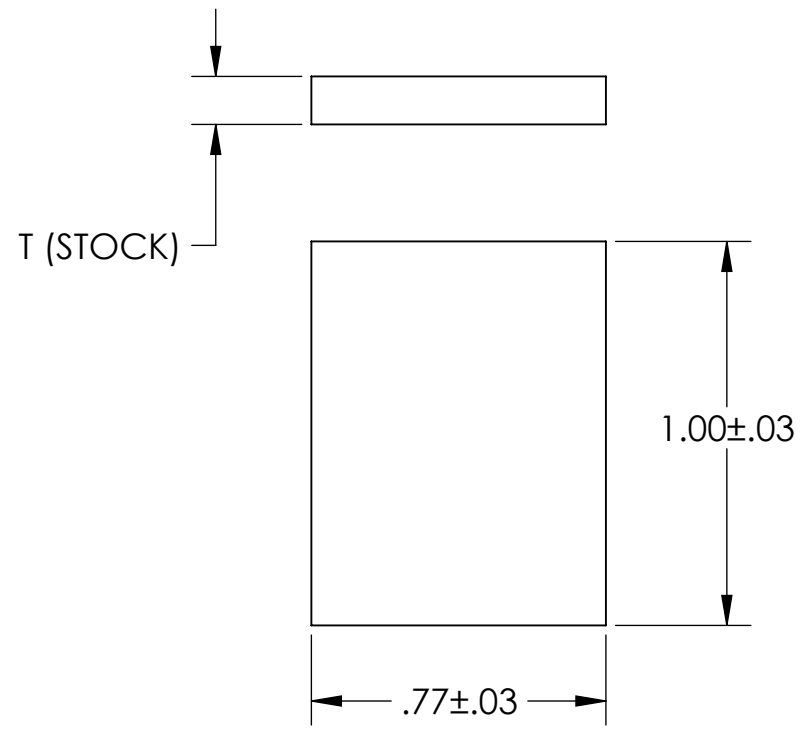
D1201285 OMC V BAFFLE ASSEMBLY, PART PDM REV: X-001, DRAWING PDM REV: X-000

REV.	DATE	DCN #	DRAWING TREE #
v1	13 DEC 2012	E1201107-x0	-
-	-	-	-
-	-	-	-

**ITEM 1**



**ITEM 2**



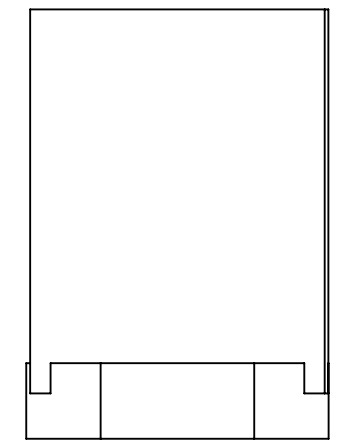
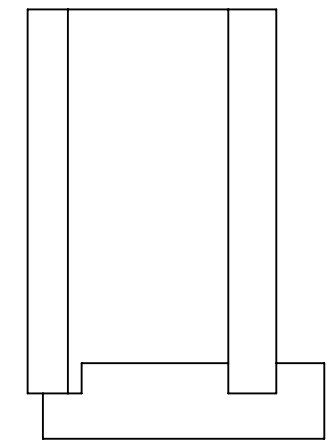
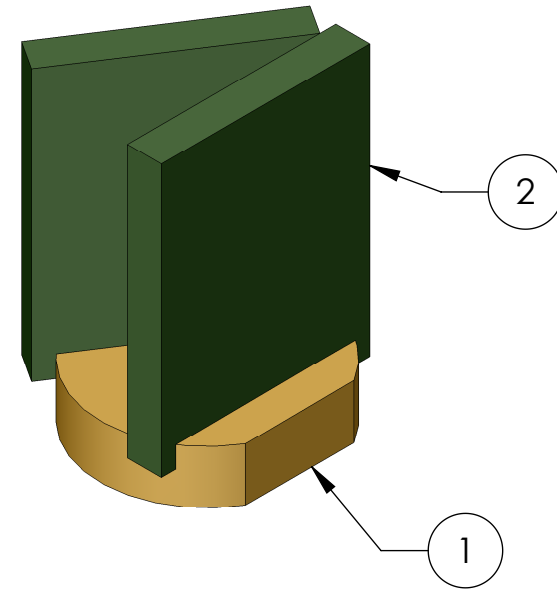
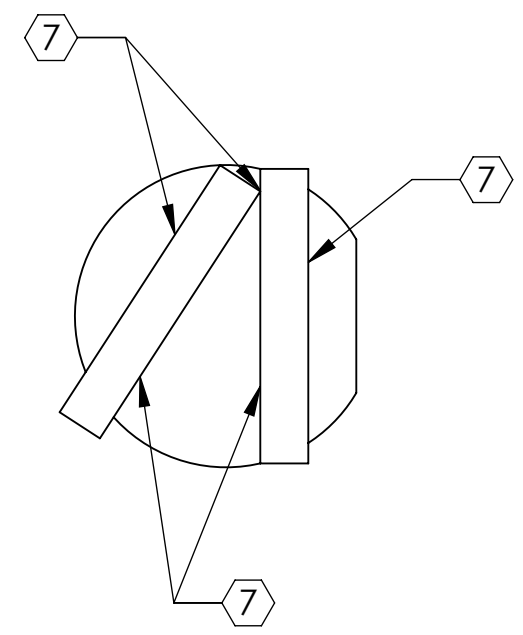
NOTES CONTINUED:

5. BAG AND TAG WITH THE PART AND SERIAL NUMBER. SERIAL NUMBERS START WITH 001.

6. CLEAN ITEMS 1 AND 2 TO REMOVE OILS AND CONTAMINANTS PRIOR TO BONDING. THE ASSEMBLY WILL BE USED IN A ULTRA HIGH VACUUM SYSTEM SO CLEANLINESS IS CRITICAL.

⑦ BOND ITEMS 1 AND 2 AT THE LOCATIONS SHOWN WITH MASTERBOND EP30-2 ACCORDING TO THE MANUFACTURER'S INSTRUCTIONS.

8. DO NOT DAMAGE OR SCATCH THE COMPONENTS, PARTICULARLY THE BOTTOM OF ITEM 1 AND THE INWARD FACING SURFACES OF ITEM 2. THE CUT EDGES OF ITEMS 1 AND 2 DO NOT REQUIRE POLISHING.



ITEM NO.	DESCRIPTION	MATERIAL	QTY.
1	D1201287 OMC V BAFFLE, BASE	OPTOSIGMA 045-0355 FUSED SILICA WINDOW	1
2	D1201286 OMC V BAFFLE, BLACK GLASS	SHADE 14 WELDING GLASS	2

**NOTES AND TOLERANCES: (UNLESS OTHERWISE SPECIFIED)**

DIMENSIONS ARE INCHES  
 TOLERANCES:  
 .XX ± .01  
 .XXX ± .005  
 ANGULAR ± 1°

1. INTERPRET DRAWING PER ASME Y14.5-1994.  
 2. REMOVE ALL SHARP EDGES, .005-.015  
 3. DO NOT SCALE FROM DRAWING.  
 4. ALL MACHINING FLUIDS MUST BE FULLY SYNTHETIC, FULLY WATER SOLUBLE AND FREE OF SULFUR, SILICONE, AND CHLORINE.

**LIGO** CALIFORNIA INSTITUTE OF TECHNOLOGY MASSACHUSETTS INSTITUTE OF TECHNOLOGY

**ADVANCED LIGO** SUB-SYSTEM **ISC**

**OMC V BAFFLE ASSY**

MATERIAL: SEE BOM      FINISH: N/A μinch      NEXT ASSY: D1201439

DESIGNER: J.LEWIS      DRAFTER: J.LEWIS      CHECKER:      APPROVAL:      DATE: 13 DEC 2012

SIZE: **B**      DWG. NO.: **D1201285**      REV.: v1

SCALE: 2:1      PROJECTION:      SHEET 1 OF 1